

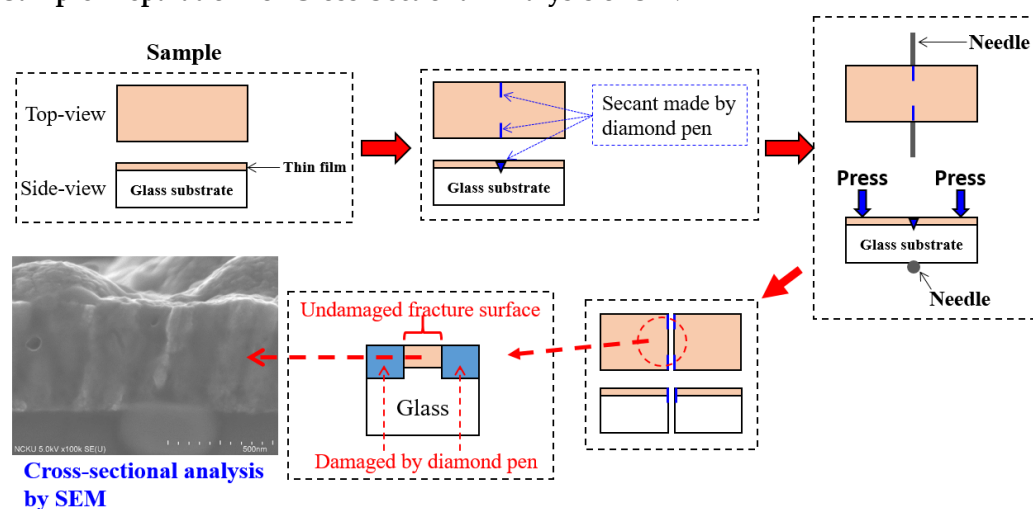
Supplementary Materials: Structural, Optical, and Electrical Properties of Copper Oxide Films Grown by the SILAR Method with Post-Annealing

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Sample Preparation for Cross-Sectional Analysis of SEM



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Figure S1. Graphical explanation of how to prepare the samples for cross-sectional analysis of SEM.

Sample Preparation for Hall Effect Measurement

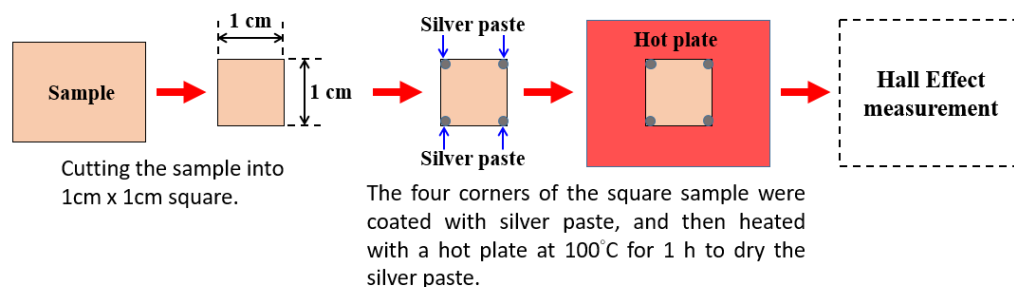


Figure S2. Graphical explanation of how to prepare the samples for Hall Effect measurement.